

**NATIONAL UNIVERSITY OF SINGAPORE**

**EXAMINATION FOR**  
(Semester I: 2011/2012)

**EE2021 –DEVICES AND CIRCUITS**

November/December 2011 - Time Allowed: 2.5 Hours

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**INSTRUCTIONS TO CANDIDATES:**

1. This paper contains **FOUR (4)** questions and comprises **SIXTEEN (16)** printed pages.
2. Answer all questions. **Start each question on a new page.**
3. All questions carry equal marks.
4. This is a **CLOSED BOOK** examination.
5. Programmable calculators are allowed in this examination.
6. The following information can be used where applicable:

Elementary charge	$e$	=	$1.602 \times 10^{-19} \text{ C}$
Boltzmann constant	$k$	=	$1.381 \times 10^{-23} \text{ J K}^{-1}$
		=	$8.618 \times 10^{-5} \text{ eV K}^{-1}$
Thermal energy ( $T = 300 \text{ K}$ )	$kT$	=	$0.0259 \text{ eV}$
Thermal voltage ( $T = 300 \text{ K}$ )	$V_t$	=	$0.0259 \text{ V}$
Permittivity of free space	$\epsilon_0$	=	$8.854 \times 10^{-14} \text{ F cm}^{-1}$

**For silicon at 300 K:**

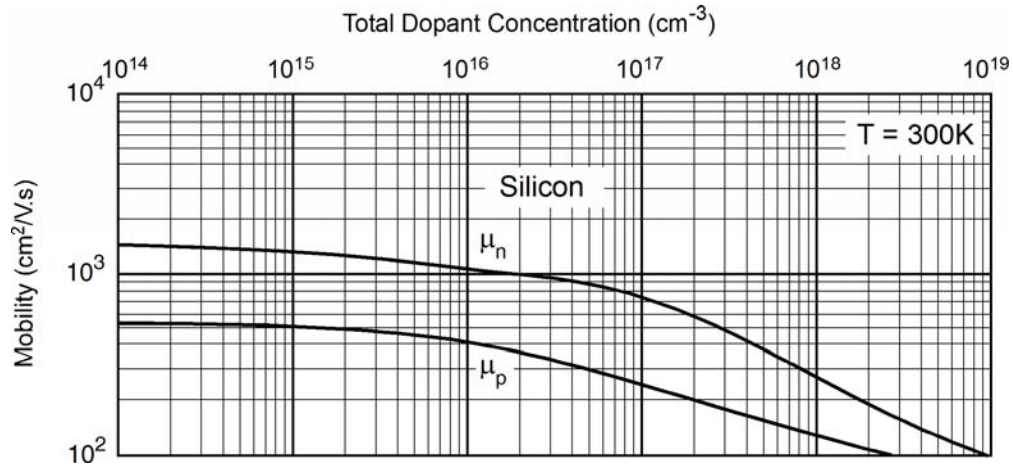
Intrinsic carrier concentration	$n_i$	=	$1.5 \times 10^{10} \text{ cm}^{-3}$
Relative permittivity of silicon	$\epsilon_r (\text{Si})$	=	11.7
Relative permittivity of silicon dioxide	$\epsilon_r (\text{SiO}_2)$	=	3.9

7. Formulas and other information are given in the APPENDIX for your reference.

- Q.1** (a) A piece of silicon is uniformly doped with  $8 \times 10^{15} \text{ cm}^{-3}$  acceptors and  $2 \times 10^{15} \text{ cm}^{-3}$  donors. The silicon is at thermal equilibrium at a temperature  $T = 300 \text{ K}$ . Calculate the conductivity of the silicon sample.

You may make use of the carrier mobility versus dopant concentration data given in Figure Q.1.1.

**[4 marks]**



**Figure Q.1.1:** Electron ( $\mu_n$ ) and hole ( $\mu_p$ ) mobilities in silicon at 300 K, as a function of total dopant concentration.

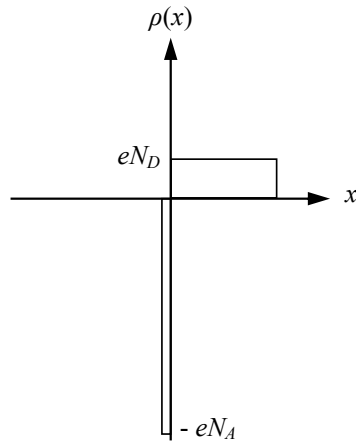
- (b) The silicon sample is uniformly illuminated with light, such that the steady state concentrations of the excess electrons and holes generated are each equal to  $10^{14} \text{ cm}^{-3}$ . The temperature  $T = 300 \text{ K}$ . What is the conductivity of the sample?

**[4 marks]**

- (c) The lifetimes of the excess electrons and holes are, respectively,  $\tau_n = 10^{-4} \text{ s}$ ,  $\tau_p = 10^{-3} \text{ s}$ . At time  $t = 0 \text{ s}$ , the illumination is switched off. Calculate the excess electron and hole concentrations at time  $t = 10^{-3} \text{ s}$ . Hence calculate the conductivity of the silicon sample at  $t = 10^{-3} \text{ s}$ .

**[4 marks]**

- (d) Figure Q.1.2 shows a sketch (not to scale) of the charge density profile,  $\rho(x)$ , in the space charge region (SCR) of a silicon p-n junction diode, at thermal equilibrium. The doping,  $N_A$ , on the p-type side is much greater than the doping,  $N_D$ , on the n-type side.



**Figure Q.1.2** : Charge density profile of a p-n junction (not to scale).

Sketch the electric field profile  $E(x)$  in the SCR of the p-n junction. Your sketch need not be to scale, but should be consistent with the charge density profile.

**[4 marks]**

- (e) Show that the magnitude of the maximum electric field,  $E_{max}$ , in the p-n junction at equilibrium can be expressed approximately as

$$E_{max} = \left[ \frac{2eV_{bi}}{\epsilon_0 \epsilon_r} \times N_D \right]^{1/2}.$$

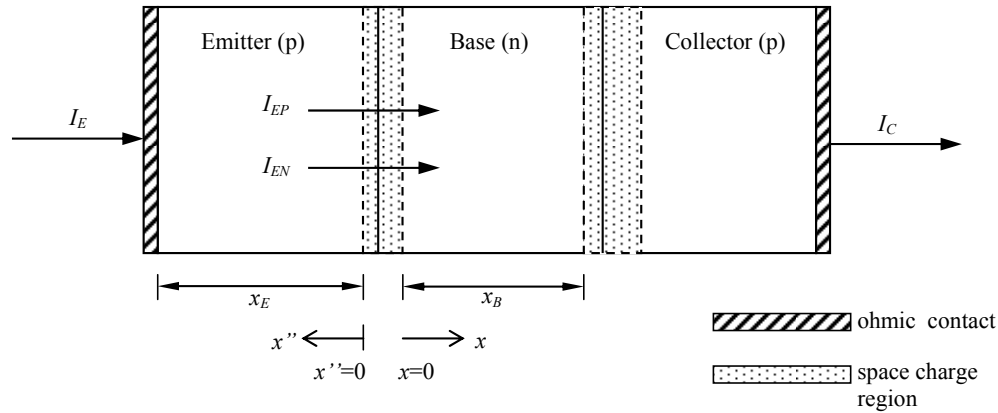
**[4 marks]**

- (f) When the p-n junction is reverse-biased, it will break down when the magnitude of the maximum electric field in the p-n junction exceeds the critical electric field,  $E_{critical}$ . For silicon,  $E_{critical} = 3 \times 10^5 \text{ V cm}^{-1}$ . The reverse bias voltage at which breakdown occurs is called the breakdown voltage.

Determine the doping,  $N_D$ , on the n-type side of the p-n junction such that the breakdown voltage is 500 V. State clearly any approximation you made in your calculations.

**[5 marks]**

**Q.2** Figure Q.2.1 is a schematic diagram of the active region of a **p-n-p** bipolar junction transistor.



**Figure Q.2.1** : Schematic diagram of the active region of a p-n-p bipolar junction transistor.

The bipolar transistor has the following specifications :

Emitter doping,  $N_{AE} = 10^{19} \text{ cm}^{-3}$ ,

Base doping,  $N_{DB} = 10^{17} \text{ cm}^{-3}$ ,

Minority carrier diffusivity in the emitter,  $D_{nE} = 2.5 \text{ cm}^2 \text{ s}^{-1}$ ,

Minority carrier diffusivity in the base,  $D_{pB} = 10 \text{ cm}^2 \text{ s}^{-1}$ ,

Minority carrier diffusion length in the emitter,  $L_{nE} = 5 \times 10^{-6} \text{ cm}$ ,

Minority carrier diffusion length in the base,  $L_{pB} = 2 \times 10^{-3} \text{ cm}$ ,

Cross-sectional area,  $A = 0.01 \text{ cm}^2$ .

The bipolar transistor is biased in the forward active mode, with an emitter-base voltage,  $V_{EB} = 0.6 \text{ V}$ , and a collector-base voltage,  $V_{CB} = -5 \text{ V}$ . Under these conditions, the widths of the neutral regions in the emitter and the base,  $x_E$  and  $x_B$  respectively, are each equal to  $5 \times 10^{-5} \text{ cm}$ .

- (a) Determine the concentrations of the excess electrons at  $x'' = 0$ , and excess holes at  $x = 0$ , respectively.

[4 marks]

- (b) Sketch, and explain briefly, the shapes of the excess minority carrier profiles,  $\delta n_E(x'')$  and  $\delta p_B(x)$  in the emitter and the base, respectively.

[6 marks]

- (c) Calculate  $I_{En}$  and  $I_{Ep}$ , where  $I_{En}$  is the component of the emitter current due to the injection of electrons from the base into the emitter, and  $I_{Ep}$  is the component of the emitter current due to the injection of holes from the emitter into the base.

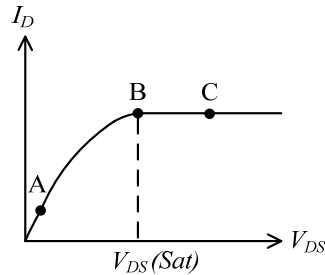
[4 marks]

- (d) Assume that recombination of excess carriers in the base is negligible, calculate the emitter current,  $I_E$ , and the collector current  $I_C$ .

[2 marks]

- (e) A silicon n-channel MOSFET has the following dimensions : length,  $L = 2 \mu\text{m}$ , width,  $W = 10 \mu\text{m}$ , thickness of the silicon dioxide under the gate,  $t_{ox} = 10 \text{ nm}$ . The mobility of the electrons in the channel is  $500 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ . The threshold voltage,  $V_{TH} = 0.5 \text{ V}$ .

The source of the MOSFET is grounded and a voltage of  $3 \text{ V}$  is applied to the gate. The  $I_D - V_{DS}$  characteristic of the MOSFET is shown in Figure Q.2.2.



**Figure Q.2.2.** : The  $I_D - V_{DS}$  characteristic of the n-channel MOSFET at a given gate bias of  $3 \text{ V}$ .

Calculate the gate oxide capacitance per unit area,  $C_{ox}$ , of the MOSFET.

Determine the drain current  $I_D$  that corresponds to point “B” in the above characteristic.

**[5 marks]**

- (f) For operation corresponding to point “B” in Figure Q.2.2, sketch the cross-sectional view of the MOSFET showing the MOS structure including the channel inversion layer and the depletion layer. The shape of the channel inversion layer must be qualitatively correct in your sketch.

**[4 marks]**

## Q.3

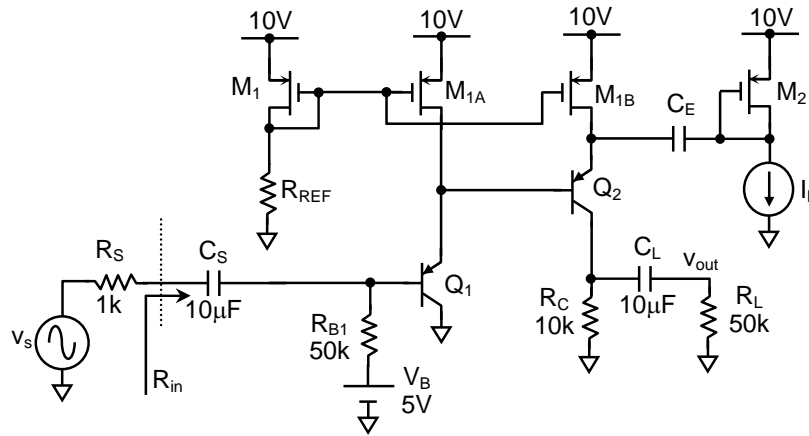


Figure Q.3 : Multistage amplifier circuit.

A multistage amplifier is shown in Figure Q.3. You may assume that the body and the source terminal of each of the PMOS are connected together, i.e., no body effect for PMOS. You may also assume the following device parameters and that all pnp BJT and PMOS devices are identical:

- $\beta=100$ ,  $V_A=100$ ,  $C_\pi=4.9\text{pF}$ ,  $C_\mu=1.7\text{pF}$ .
- $K_p=2\text{mA/V}^2$ ,  $V_{THP}=-1\text{V}$ ,  $\lambda_p=0.001\text{V}^{-1}$ .

- (a) Design  $R_{REF}$  such that  $I_{D,M1}$  is  $500\mu\text{A}$ . Work out the small signal AC parameters of  $Q_1$ .

[5 marks]

- (b) Identify the two stage amplifier configuration.

[2 marks]

- (c) Obtain the expression for the small signal gain ( $v_{out}/v_s$ ) of the amplifier. You can use the variable  $g_{m,M2}$  in your expression as  $I_B$  is not given.

[8 marks]

- (d) Estimate the value of  $I_B$  in order to have a gain ( $v_{out}/v_s$ ) of -20.

[6 marks]

- (e) Design  $C_E$  such that  $f_L$  is 100Hz.

[4 marks]

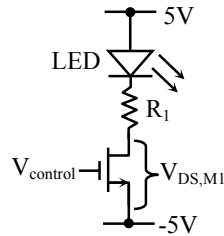
**Q.4** (a) Draw the pull-up and pull-down network for the following logic function:

$$Y = \overline{(A + B \cdot C)} \cdot D \cdot \overline{(E + F)} \quad [8 \text{ marks}]$$

- (i) Define the respective logic values of A, B, C, D, E and F such that it will lead to the worst case  $t_{\text{pHL}}$ . [2 marks]

- (ii) Assume that all NMOS transistors in the designed pull-down network have a sizing of  $2n$ , and that the NMOS transistor in the symmetric inverter has a sizing of  $n$ . Find the relationship between  $t_{\text{pHL,logic}}$  and  $t_{\text{pHL,inv}}$ . [3 marks]

- (b) (i) The LED circuit shown in Figure Q4 is a small part of a Christmas light decoration. The LED will light up if a current of 1 mA flows through it. Assuming that the LED has an I–V characteristic similar to that of normal diodes, estimate the resistance ( $R_1$ ) needed to obtain the 1 mA current. You can assume that when the MOSFET turns on,  $V_{\text{DS,M1}}$  is negligible. [2 marks]



**Figure Q.4 :** LED circuit.

- (ii) Suggest an opamp-based circuit that can generate the proper  $V_{\text{control}}$  such that the LED in part (i) will blink a few times per minute. [5 marks]

- (iii) For the proposed opamp circuit in (ii), select the component values such that the LED will blink 3 times per minute. [5 marks]

**END OF QUESTIONS**

## APPENDIX

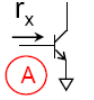
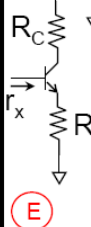
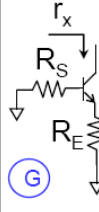
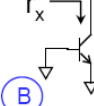
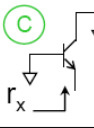

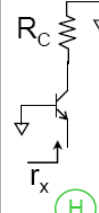
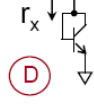
1. Law of mass action	$p_0 n_0 = n_i^2$
2. Space-charge density	$\rho = e(p + N_D^+ - n - N_A^-)$
3. Conductivity	$\sigma = e(n\mu_n + p\mu_p)$
4. Current densities	$J_n = en\mu_n E + eD_n \frac{dn}{dx}$ $J_p = ep\mu_p E - eD_p \frac{dp}{dx}$
5. Einstein Relation	$\frac{D_n}{\mu_n} = \frac{D_p}{\mu_p} = \frac{kT}{e}$
6. Decay of excess minority carrier concentration as a function of <u>time</u> , under low-level injection conditions, where $\tau$ is the minority carrier lifetime.	$\delta n(t) = \delta n(0) \exp\left(\frac{-t}{\tau}\right)$ $\delta p(t) = \delta p(0) \exp\left(\frac{-t}{\tau}\right)$
7. Poisson's equation (Gauss's Law)	$\frac{dE}{dx} = -\frac{d^2\phi}{dx^2} = \frac{\rho(x)}{\epsilon_r \epsilon_0}$
8. Built-in potential of an abrupt p-n junction diode.	$V_{bi} = \frac{kT}{e} \ln\left(\frac{n_{n0}}{n_{p0}}\right) = \frac{kT}{e} \ln\left(\frac{p_{p0}}{p_{n0}}\right)$ $= \frac{kT}{e} \ln\left(\frac{N_A N_D}{n_i^2}\right)$
9. Space-charge region width of an unbiased abrupt pn junction diode.	$W = \left[ \frac{2\epsilon_r \epsilon_0 V_{bi}}{e} \left( \frac{N_A + N_D}{N_A N_D} \right) \right]^{\frac{1}{2}}$
10. Magnitude of the maximum electric field in an abrupt pn junction diode.	$E_{\max} = \frac{e N_A N_D}{\epsilon_r \epsilon_0 (N_A + N_D)} W$



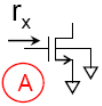
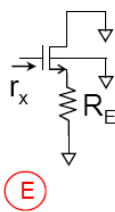
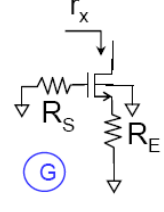
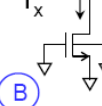
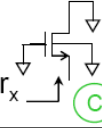
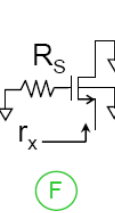
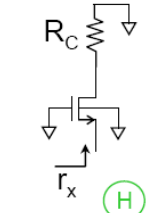
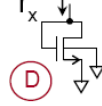
11. Excess carrier concentration with respect to <u>position</u> for a long-base abrupt pn junction diode under low-level injection conditions	$\delta n_p(x') = \delta n_p(0) \cdot \exp\left(-\frac{x'}{L_n}\right)$ $\delta p_n(x'') = \delta p_n(0) \cdot \exp\left(-\frac{x''}{L_p}\right)$
12. Excess carrier concentration at the edges of the space-charge region of an abrupt pn junction diode under low-level injection conditions.	$\delta n_p(0) = n_{p0} \left[ \exp\left(\frac{eV}{kT}\right) - 1 \right]$ $\delta p_n(0) = p_{n0} \left[ \exp\left(\frac{eV}{kT}\right) - 1 \right]$
13. Minority carrier diffusion lengths.	$L_n = \sqrt{D_n \tau_n}$ $L_p = \sqrt{D_p \tau_p}$
14. Ideal diode current density-voltage equation for an abrupt, pn junction diode.	$J = J_s \left[ \exp\left(\frac{eV_a}{kT}\right) - 1 \right], \text{ where } V_a \text{ is the applied voltage, and } J_s = J_{s,p} + J_{s,n}$
14a. For “long” n-type neutral region	$J_{s,p} = e \frac{D_p}{L_p} p_{n0}$
14b. For “short” n-type neutral region	$J_{s,p} = e \frac{D_p}{W_n} p_{n0}$
14c. For “long” p-type neutral region	$J_{s,n} = e \frac{D_n}{L_n} n_{p0}$
14d. For “short” p-type neutral region	$J_{s,n} = e \frac{D_n}{W_p} n_{p0}$
15. Junction capacitance of an abrupt pn junction diode.	$C_j = \frac{\epsilon_0 \epsilon_r (Si) A}{W}$
16. Incremental resistance of a pn junction diode	$r_d = \frac{V_t}{I_Q}$
17a. Emitter injection efficiency of an <b>npn</b> bipolar junction transistor (short base and long emitter)	$\gamma = \frac{I_{En}}{I_E} = \frac{1}{1 + \frac{D_E x_B N_B}{D_B L_E N_E}}$

17b. Emitter injection efficiency of an <b>npn</b> bipolar junction transistor (short base and short emitter)	$\gamma = \frac{I_{En}}{I_E} = \frac{1}{1 + \frac{D_E x_B N_B}{D_B x_E N_E}}$
18a. Base transport factor of an <b>npn</b> bipolar transistor (general definition)	$\alpha_T = \frac{I_{Cn}}{I_{En}}$
18b. Base transport factor of an <b>npn</b> bipolar transistor (short base)	$\alpha_T = 1 - \frac{1}{2} \left( \frac{x_B}{L_n} \right)^2$
<b>Note</b> : For <b>pnp</b> bipolar transistors, interchange the roles of the electrons and holes.	
19. Common base current gain of a bipolar junction transistor	$\alpha = \frac{I_C}{I_E}$
20. Common emitter current gain of a bipolar junction transistor.	$\beta = \frac{I_C}{I_B} = \frac{\alpha}{1 - \alpha}$
21. Gate oxide capacitance of a MOSFET (per unit area of the capacitor)	$C_{ox} = \frac{\epsilon_{ox}}{t_{ox}} = \frac{\epsilon_o \times \epsilon_r (SiO_2)}{t_{ox}}$
22. Drain current in the linear region of an n-channel MOSFET	$I_D = \mu_n \frac{W}{L} C_{ox} \left[ (V_G - V_T) V_D - \frac{1}{2} V_D^2 \right]$
23. Drain current in the saturation region of an n-channel MOSFET	$I_D = \frac{1}{2} \mu_n \frac{W}{L} C_{ox} (V_G - V_T)^2$
24. Transconductance of a MOSFET	$g_m \equiv \frac{dI_D}{dV_G}$

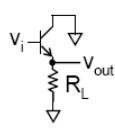
# BJT DP Summary (Table 1)

Conf	DP $r_x$	Conf	DP $r_x$	Conf	DP $r_x$
 (A)	$\frac{\beta}{g_m}$	 (E)	$r_\pi + (1 + \beta)R_E$ $\approx r_\pi(1 + g_m R_E)$	 (G)	$r_o \left\{ 1 + g_m \left[ (r_\pi + R_S) \parallel R_E \right] \left( \frac{r_\pi}{r_\pi + R_S} \right) \right\}$ If $R_S = 0$ and $r_\pi \ll R_E$ $\Rightarrow r_{x,\max} = r_o(\beta + 1)$
 (B)	$\frac{V_A}{I_C}$				
 (C)	$\frac{1}{g_m}$	 (F)	$\frac{R_S + r_\pi}{1 + \beta} \parallel r_o$ $\approx \frac{R_S}{1 + \beta} + \frac{1}{g_m}$	 (H)	$\frac{1}{g_m} \times \frac{r_o + R_C}{r_o + R_C / \beta}$
 (D)	$\frac{1}{g_m}$				

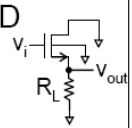
# MOS DP Summary (Table 2)

Conf	DP $r_x$	Conf	DP $r_x$	Conf	DP $r_x$
 (A)	$\infty$	 (E)	$\infty$	 (G)	$r_o [1 + (g_m - g_{mb})R_E]$
 (B)	$\frac{1}{\mu_D}$				
 (C)	$\frac{1}{g_m - g_{mb}}$	 (F)	$\frac{1}{g_m - g_{mb}}$	 (H)	$\frac{1}{g_m - g_{mb}} \times \frac{r_o + R_C}{r_o}$
 (D)	$\frac{1}{g_m}$				

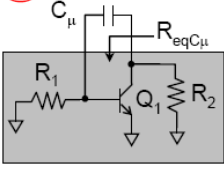
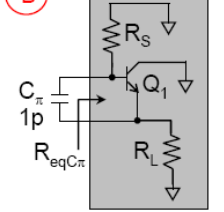
## BJT Summary (Table 3)

BJT	$G_m$	$A_v$
CE (A)	$g_m$	Derive Based on 2-ports Network
CB (B)	$-g_m$	Derive Based on 2-ports Network
CC (C) 	Not Applicable	$\frac{g_m R_L}{1 + g_m R_L}$
CE with Emitter Degeneration (D)	$\frac{g_m}{1 + g_m R_E}$	Derive Based on 2-ports Network

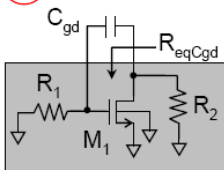
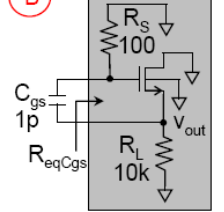
## MOS Summary (Table 4)

MOS	$G_m$	$A_v$
CS (A)	$g_m$	Derive Based on 2-ports Network
CG (B)	$-(g_m - g_{mb})$ <i>Drop <math>g_{mb}</math> if no body effect</i>	Derive Based on 2-ports Network
CD (C) 	Not Applicable	$\frac{g_m R_L}{1 + (g_m - g_{mb}) R_L} \approx \frac{g_m}{g_m - g_{mb}}$ <i>Drop <math>g_{mb}</math> if no body effect</i>
CS with $R_E$ (D)	$\frac{g_m}{1 + (g_m - g_{mb}) R_E}$ <i>Drop <math>g_{mb}</math> if no body effect</i>	Derive Based on 2-ports Network

## BJT Frequency Summary Table (Table 5)

<p>(A)</p> 	<p><math>R_{eqC_{\mu}}</math></p> $R_{eqi} = R_1 // r_{\pi,Q1} \quad R_{eqo} = R_2 // r_{o,Q1}$ $R_{eqC_{\mu}} = R_{eqi} + (1 + g_{m,Q1} R_{eqi}) R_{eqo}$ $= (R_1 // r_{\pi,Q1}) + [1 + g_m (R_1 // r_{\pi,Q1})] (R_2 // r_{o,Q1})$ <p>Miller Theorem Validity :</p> $g_{m,Q1} R_{eqi} \gg 1$	<p><math>\tau_{eqC_{\mu}}</math></p> $\tau_{eqC_{\mu}} = C_{\mu} R_{eqC_{\mu}}$
<p>(B)</p> 	<p><math>R_{eqC_{\pi}}</math></p> $R_{eqC_{\pi}} = r_{\pi,Q1} // \left( \frac{R_S + (R_L // r_{o,Q1})}{1 + g_{m,Q1} (R_L // r_{o,Q1})} \right)$	<p><math>\tau_{eqC_{\pi}}</math></p> $\tau_{eqC_{\pi}} = C_{\pi} R_{eqC_{\pi}}$

## MOS Frequency Summary Table (Table 6)

<p>(A)</p> 	<p><math>R_{eqC_{gd}}</math></p> $R_{eqi} = R_1 \quad R_{eqo} = R_2 // r_{o,M1}$ $R_{eqC_{gd}} = R_{eqi} + (1 + g_{m,M1} R_{eqi}) R_{eqo}$ $= R_1 + (1 + g_m R_1) (R_2 // r_{o,M1})$ <p>Miller Theorem Validity :</p> $g_{m,M1} R_{eqi} \gg 1$	<p><math>\tau_{eqC_{gd}}</math></p> $\tau_{eqC_{gd}} = C_{gd} R_{eqC_{gd}}$
<p>(B)</p> 	<p><math>R_{eqC_{gs}}</math></p> $R_{eqC_{gs}} = \frac{R_S [1 - g_{mb,M1} (R_L // r_{o,M1})] + (R_L // r_{o,M1})}{1 + (g_{m,M1} - g_{mb,M1}) (R_L // r_{o,M1})}$	<p><math>\tau_{eqC_{gs}}</math></p> $\tau_{eqC_{gs}} = C_{gs} R_{eqC_{gs}}$

## 1) Logic Gates:

For K transistor in series:

$$\left(\frac{W}{L}\right)_{eq} = \left[ \left(\frac{W}{L}\right)_1^{-1} + \left(\frac{W}{L}\right)_2^{-1} + \dots + \left(\frac{W}{L}\right)_K^{-1} \right]^{-1}$$

For K transistor in parallel:

$$\left(\frac{W}{L}\right)_{eq} = \left(\frac{W}{L}\right)_1 + \left(\frac{W}{L}\right)_2 + \dots + \left(\frac{W}{L}\right)_K$$

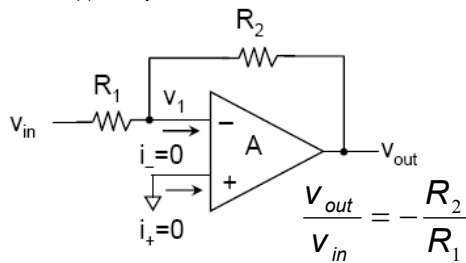
## 2) SCTC and OCTC:

$$2\pi f_L = b_1 = \sum \frac{1}{\tau_i}$$

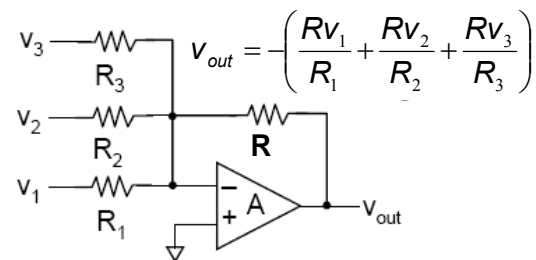
$$2\pi f_U = \frac{1}{a_1} = \frac{1}{\sum \tau_i}$$

## 3) Opamp Circuits:

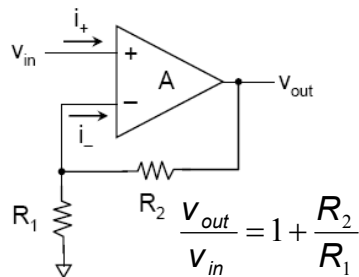
## Inverting Amplifier



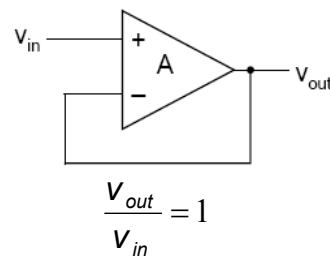
## Summing Amplifier



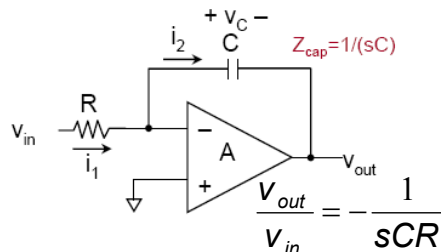
## Non-inverting Amplifier



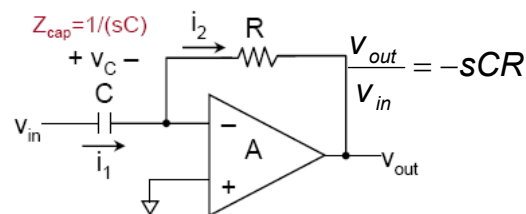
## Buffer



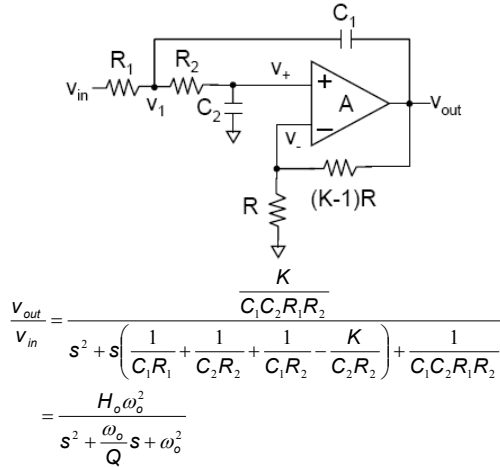
## Integrator



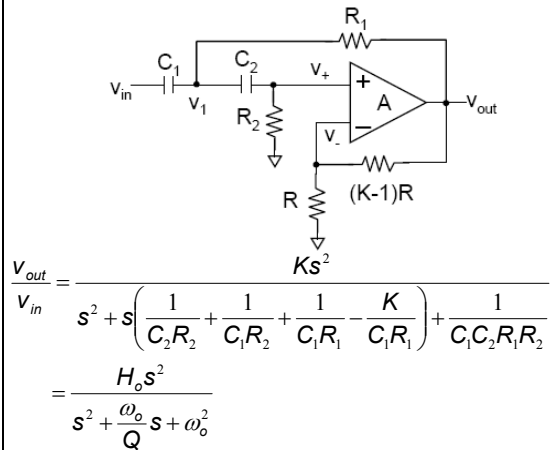
## Differentiator



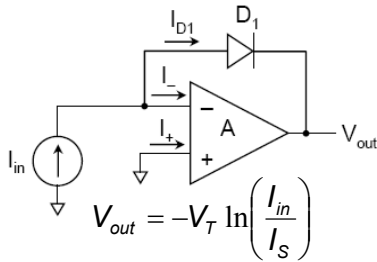
## SK Lowpass Filter



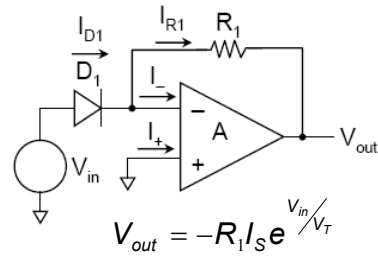
## SK Highpass Filter



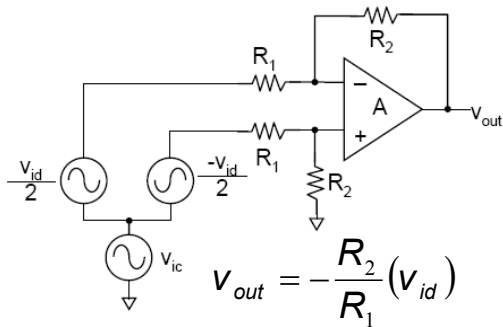
## Logarithm Amplifier



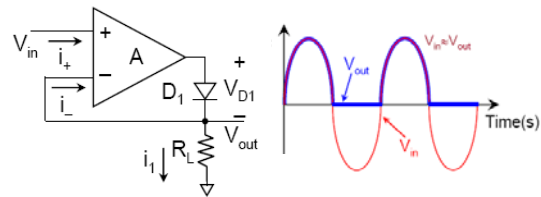
## Exponential Amplifier



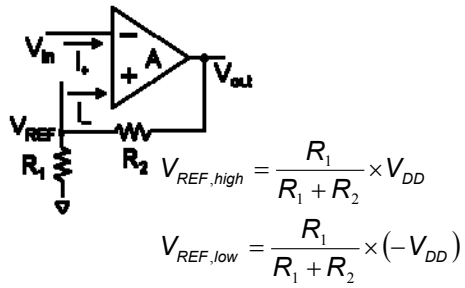
## Instrumentation Amplifier



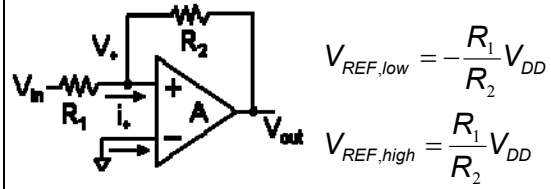
## Super Diode



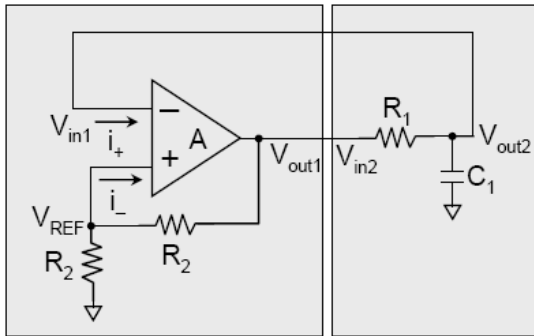
## Inverting Comparator with Hysteresis



## Comparator with Hysteresis



## Bistable Multivibrator



$$T = 2C_1 R_1 \ln(3)$$

**END OF PAPER**